

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)				ATTY. DOCKET NO. 1268-260		U.S. APPLICATION NO. Not yet assigned		
				APPLICANT Einar NYGARD				
				FILING DATE herewith		GROUP		
U.S. PATENT DOCUMENTS								
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE		
/SCS/	5 254 868	10/19/1993	SAITO					
/SCS/	5 998 292	12/07/1999	BLACK et al					
/SCS/	4 547 792	10/15/1985	SCLAR					
/SCS/	4 857 746	08/15/1989	KUHLMANN et al					
/SCS/	5 132 539	07/21/1992	KWASNICK et al					
/SCS/	6 416 218 B1	07/09/2002	CHEUNG					
FOREIGN PATENT DOCUMENTS								
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation		
						Yes	No	
/SCS/	03/083944 A1	10/09/2003	WO					
/SCS/	1 045 450 A3	05/29/2002	EP					
/SCS/	0 537 514 A2	04/21/1993	EP					
/SCS/	1 253 442 A1	10/30/2002	EP					
/SCS/	61 128 564 A2	06/16/1986	JP			abstract		
/SCS/	02/067014 A1	08/29/2002	wo					
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
/SCS/	Tewksbury et al; "Cointegration of Optoelectronics and Submicron CMOS"; Wafer Scale Information, 1993. Proceedings., Fifth Annual IEEE International Conference on San Francisco, CA USA; January 20, 1993; pages 358-367; XP010067696							
/SCS/	Flack et al; "Lithographic Manufacturing Techniques for Wafer Scale Integration"; Wafer Sale Integration, 1992. Proceedings., Fourth International Conference on San Francisco, CA USA, January 22, 1992; pages 4-13, XP010026528							
/SCS/	Banthien et al; "A Vertically Integrated High Resolution Active Pixel Image Sensor for Deep Submicron CMOS Processes; presented to 1999 IEEE Workshop on CCDs and Advance Image Sensors, Nagano Japan, June 10-12, 1999							
EXAMINER			/Seung C Sohn/		DATE CONSIDERED			10/29/2007

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.